

## Workshop on airborne chemical contamination

17<sup>th</sup> November 2020

Host: Tuomas Hieta (Gasera)



**Locations** Goto Meeting (link to be circulated before the workshop)  
Please register by **30<sup>th</sup> October 2020**

**Time zone** CET (UTC+01:00)

### Preliminary programme (20-minute talks + 5-minute questions)

10:00 *Arrival and microphone check*

10:10 *Welcome*

Tuomas Hieta, Gasera and Geoffrey Barwood, NPL

### Introduction

10:30 *“Airborne chemical contamination and the link to process failure”*  
Markus Keller, Fraunhofer IPA

10:55 *“Relation between AMCs and yield from an industrial perspective”*  
Hugh E. Gotts, Air Liquide Electronics U. S. LP

### Airborne chemical contamination measurement technology

11:20 *“Overview of AMC measurement technologies and trends”*  
Graham Leggett, LI-COR Biosciences

11:45 *“Laser-spectrometric AMC detection – methods, uncertainties, and metrological traceability”*  
Zhechao Qu and Olav Werhahn, PTB

12:10 40-minute lunch break

12:50 *“AMC Monitoring - From Lab to Fab”*  
Jens Herbig, IONICON

13:25 *“Frontiers in optical gas sensing”*  
Anne Curtis, NPL

Generating, sampling and handling of airborne chemical contaminants

13:50 *“Reliable generation and sampling of HCl, NH<sub>3</sub> and H<sub>2</sub>O”*  
Michael Ward, NPL

14:15 15-minute coffee break

14:30 *“Preparation and sampling methods for metrological traceability of measurements of HCl and HF”*  
Heleen Meuzelaar, VSL

14:55 *“Measuring HF, NH<sub>3</sub> and HCl in clean rooms”*  
Timo Rajamäki, VTT / OPTOSEVEN

15:20 *Closing Remarks*